

IN THE CLAIMS

Please amend the claims as follows:

Claim 1 (Currently Amended) A substrate processing apparatus, comprising:

a carrier block ~~(B1)~~ including a carrier placement portion ~~(21)~~ to/from which a substrate carrier ~~(C)~~ storing a plurality of substrates is loaded/unloaded, and first transfer means ~~(22)~~ for performing delivery of the substrate with respect to the substrate carrier ~~(C)~~ placed on the carrier placement portion ~~(21)~~;

second transfer means ~~(23)~~ provided adjacent to the carrier block ~~(B1)~~ and for transferring the substrate along a linear transfer path;

a first delivery stage ~~(24)~~ for performing delivery of the substrate between said first transfer means ~~(22)~~ and said second transfer means ~~(23)~~;

a plurality of process blocks ~~(B0, B3, B4)~~ arranged along said transfer path and freely attachable/detachable with respect to a main body of the apparatus; and

an interface portion ~~(B5)~~ located between said transfer path and a light exposure machine;

each process block ~~(B0, B3, B4)~~ including a coating unit ~~(32)~~ for applying a resist solution to the substrate, a developing unit ~~(33)~~ for performing developing processing on the substrate after exposure to light, a heating unit ~~(PEB, LHP, PAB)~~ for heating the substrate, third transfer means ~~(31)~~ for transferring the substrate between the units, and a second delivery stage ~~(TRS1, TRS2)~~ for performing delivery of the substrate between said second transfer means ~~(23)~~ and said third transfer means ~~(31)~~,

said transfer path extending from said interface portion ~~(B5)~~ to said carrier block ~~(B1)~~, with said plurality of process blocks ~~(B0, B3, B4)~~ arranged on only one side of said transfer path, and each of said plurality of process blocks ~~(B0, B3, B4)~~ performing same processing, and

application of the resist solution to the substrate and/or the developing processing after exposure to light being performed in units of the respective process blocks (~~B0, B3, B4~~).

Claim 2 (Currently Amended): The substrate processing apparatus according to claim 1, wherein an interface portion (~~B5~~) to which a light exposure device (~~B6~~) is connected is connected to a side of said transfer path opposite to a side connected to the carrier block (~~B1~~).

Claim 3 (Currently Amended): The substrate processing apparatus according to claim 1, wherein an interface portion (~~B5~~) to which a light exposure device (~~B6~~) is connected is connected to a side of said transfer path opposite to a side connected to the process blocks (~~B0, B3, B4~~).

Claim 4 (Currently Amended): A substrate processing apparatus, comprising:
a carrier block (~~B1~~) including a carrier placement portion (~~21~~) to/from which a substrate carrier (~~C~~) storing a plurality of substrates is loaded/unloaded, and first transfer means (~~22~~) for performing delivery of the substrate with respect to the substrate carrier (~~C~~) placed on the carrier placement portion (~~21~~);

second transfer means (~~23~~) provided adjacent to the carrier block (~~B1~~) and for transferring the substrate along a linear transfer path;

a first delivery stage (~~24~~) for performing delivery of the substrate between said first transfer means (~~22~~) and said second transfer means (~~23~~);

a plurality of process blocks (~~B0, B3, B4~~) arranged along said transfer path and freely attachable/detachable with respect to a main body of the apparatus; and

an interface portion (~~B5~~) located between said transfer path and a light exposure machine;

each process block (~~B0, B3, B4~~) including a liquid process unit (~~U1~~) performing processing with a chemical solution on the substrate, a heating unit (~~PEB, LHP, PAB~~) for heating the substrate, third transfer means (~~31~~) for transferring the substrate between the units, and a second delivery stage (~~TRS1, TRS2~~) for performing delivery of the substrate between said second transfer means (~~23~~) and said third transfer means (~~31~~),

said transfer path extending from said interface portion (~~B5~~) to said carrier block (~~B1~~), with said plurality of process blocks (~~B0, B3, B4~~) arranged on only one side of said

transfer path, and each of said plurality of process blocks (~~B0, B3, B4~~) performing same processing, and

processing being performed on the substrate in units of the respective process blocks (~~B0, B3, B4~~).

Claim 5 (Currently Amended): The substrate processing apparatus according to claim 4, wherein said liquid process unit (~~U1~~) is for forming a coating film.

Claim 6 (Currently Amended): The substrate processing apparatus according to claim 4, wherein said liquid process unit (~~U1~~) is for applying a chemical solution including precursor of an insulating film to the substrate.

Claim 7 (Currently Amended): The substrate processing apparatus according to claim 4, wherein said plurality of process blocks (~~B0, B3, B4~~) are formed to have a same size in two dimensions.

Claim 8 (Currently Amended): The substrate processing apparatus according to claim 4, wherein said second transfer means (~~23~~) is provided in a transfer block extending along arrangement of the plurality of process blocks (~~B0, B3, B4~~), and each process block (~~B0, B3, B4~~) is configured to be attachable/detachable with respect to the transfer block.

Claim 9 (Currently Amended): The substrate processing apparatus according to claim 8, wherein said carrier block (~~B1~~) is capable of rotating about a rotation shaft (~~28~~) provided at an end portion of said transfer block (~~B2~~).

Claim 10 (Currently Amended): The substrate processing apparatus according to claim 8, wherein said process block (~~B0, B3, B4~~) is attached to said transfer block (~~B2~~) via a hinge (~~528~~), and rotated about said hinge (~~528~~) to be positioned in place.

Claim 11 (Currently Amended): The substrate processing apparatus according to claim 4, comprising a positioning member (~~45~~) provided at a bottom portion or a side portion of a region where said process block (~~B0, B3, B4~~) is to be arranged, for use in positioning said process block (~~B0, B3, B4~~).

Claim 12 (Currently Amended): The substrate processing apparatus according to claim 4, comprising a guide member (~~44~~) provided at a bottom portion or a side portion of a region where said process block (~~B0, B3, B4~~) is to be arranged, for use in drawing the process block (~~B0, B3, B4~~), and a positioning member (~~45~~) provided for positioning the process block (~~B0, B3, B4~~) to the guide member (~~44~~).

Claim 13 (Currently Amended): The substrate processing apparatus according to claim 4, wherein each process block (~~B0, B3, B4~~) includes a plurality of utility lines (~~41, 42~~) for taking in utilities from the outside, and connection ends (~~41a, 42a~~) of the respective utility lines (~~41, 42~~) configured to be attachable/detachable with respect to connection ends (~~41b, 42b~~) of corresponding utility lines on the outside.

Claim 14 (Currently Amended): The substrate processing apparatus according to claim 13, wherein said plurality of utility lines (~~41, 42~~) supply utilities different from each other, and each of the plurality of utility lines (~~41, 42~~) is branched on a downstream side to be guided to the respective process units.

Claim 15 (Currently Amended): The substrate processing apparatus according to claim 13, wherein the plurality of utility lines (~~41, 42~~) include a supply line of liquid for temperature regulation, a supply line of inactive gas, an electric supply line, and a signal line.

Claim 16 (Currently Amended): The substrate processing apparatus according to claim 4, wherein a connection end (~~41b, 42b~~) on an external side is provided at a lower side of the second transfer means (~~23~~), and it is configured such that when the process block (~~B0, B3, B4~~) is pressed to the second transfer means (~~23~~) side, the connection end (~~41b, 42b~~) on the external side is connected to a connection end (~~41a, 42a~~) on the process block (~~B0, B3, B4~~) side.

Claim 17 (Currently Amended): The substrate processing apparatus according to claim 16, wherein the utility lines (~~41, 42~~) further include a chemical solution supply tube.